Notice of References Cited

Application/Control No. 10/086,614	Applicant(s)/Patent Under Reexamination MIRKARIMI ET AL.		
Examiner	Art Unit		
Wesley D Markham	1762	Page 1 of 1	

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-6,767,475	07-2004	Mearini et al.	216/38
	В	US-6,295,164	09-2001	Murakami et al.	359/584
	С	US-4,904,083	02-1990	Lu et al.	356/469
	D	US-6,573,030	06-2003	Fairbairn et al.	430/323
	E	US-5,266,409	11-1993	Schmidt et al.	428/446
	F	US-5,745,286	04-1998	Hawryluk, Andrew M.	359/359
	G	US-5,508,368	04-1996	Knapp et al.	427/534
	Н	US-2002/0171922	11-2002	Shiraishi et al.	359/359
	ı	US-6,319,635	11-2001	Mirkarimi et al.	430/5
	J	US-			
	К	US-			
	L	US-			
	М	US-			

FOREIGN PATENT DOCUMENTS

	10-10-			ORLIGIT I ATENTE	7000III EI I I I	
*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N,	WO 03/036654 A1	05-2003	PCT	Yakshin et al.	-
	0 1	JP 10-300912 A	11-1998	Japan	Sasai et al.	-
1	Р					
	Q					
	R					
	S					
	Т					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Mirkarimi et al., "Investigating the growth of localized defects in thin films using gold nanospheres", Appl. Phys. Lett., Vol.77, Number 14, pages 2243-2245, October 2000
	V ,	Spiller, "Smoothing of multilayer x-ray mirrors by ion polishing", Appl. Phys. Lett., Vol.54, Number 23, pages 2293-2295, June 1989
	w	Mirkarimi et al., "An Ion-Assisted Mo-Si Deposition Process for Planarizing Reticle Substrates for Extreme Ultraviolet Lithography", Quantum Electronics Letters, Vol.37, Number 12, pages 1514-1516, December 2001
	x	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.